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- ☐ 1. **Plasma-induced charging damage to MOS capacitor structure in cyclotron-resonance plasmas**
 Friedmann, J.B.; Ma, S.-M.; McVittie, J.P.; Shohet, J.L.; Plasma Science, 1995. IEEE Conference Record - Abstracts., 1995. International Conference on 5-8 June 1995 Page(s):164
 Digital Object Identifier 10.1109/PLASMA.1995.531626
[AbstractPlus](#) | [Full Text: PDF\(112 KB\)](#) IEEE CNF
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- ☐ 2. **Prediction of plasma charging induced gate oxide damage by probe**
 Shawming Ma; McVittie, J.P.; Saraswat, K.C.; [Electron Device Letters, IEEE](#)
 Volume 18, Issue 10, Oct. 1997 Page(s):468 - 470
 Digital Object Identifier 10.1109/55.624913
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(84 KB\)](#) IEEE JNL
[Rights and Permissions](#)
- ☐ 3. **Evaluation of charge build-up in wafer processing by using with charge collecting electrodes**
 Kubo, H.; Namura, T.; Yoneda, K.; Ohishi, H.; Todokoro, Y.; [Microelectronic Test Structures, 1995. ICMTS 1995. Proceeding: International Conference on](#)
 22-25 March 1995 Page(s):5 - 9
 Digital Object Identifier 10.1109/ICMTS.1995.513936
[AbstractPlus](#) | [Full Text: PDF\(480 KB\)](#) IEEE CNF
[Rights and Permissions](#)
- ☐ 4. **Resist-related damage on ultrathin gate oxide during plasma**
 Chao-Hsin Chien; Chun-Yen Chang; Horng-Chih Lin; Tsai-Fu Ch Chiou; Liang-Po Chen; Tiao-Yuan Huang;
[Electron Device Letters, IEEE](#)
 Volume 18, Issue 2, Feb. 1997 Page(s):33 - 35
 Digital Object Identifier 10.1109/55.553034
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(64 KB\)](#) IEEE JNL
[Rights and Permissions](#)

- ☐ **5. Reduction and non-uniformity of high density plasma process: electrical degradation in MOS devices**
Pei-Jer Tzeng; Jen-Chieh Li; Chun-Chen Yeh; Kuei-Shu Chang-
Plasma Process-Induced Damage, 1999 4th International Symposium
9-11 May 1999 Page(s):100 - 103
Digital Object Identifier 10.1109/PPID.1999.798823
[AbstractPlus](#) | [Full Text: PDF\(188 KB\)](#) IEEE CNF
[Rights and Permissions](#)

- ☐ **6. The role of resist for ultrathin gate oxide degradation during**
Chao-Hsin Chien; Chun-Yen Chang; Horng-Chih Lin; Shean-Gui
Yuan Huang; Tsai-Fu Chang; Szu-Kang Hsien;
Electron Device Letters, IEEE
Volume 18, Issue 5, May 1997 Page(s):203 - 205
Digital Object Identifier 10.1109/55.568764
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(60 KB\)](#) IEEE JNL
[Rights and Permissions](#)

- ☐ **7. Sensitivity and limitations of plasma charging damage measurement on MOS capacitors structures**
Shawming Ma; Abdel-Ati, W.L.N.; McVittie, P.;
Electron Device Letters, IEEE
Volume 18, Issue 9, Sept. 1997 Page(s):420 - 422
Digital Object Identifier 10.1109/55.622516
[AbstractPlus](#) | [References](#) | [Full Text: PDF\(88 KB\)](#) IEEE JNL
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- ☐ **8. A study of wafer charging with CHARM-2 and large area capacitance**
Current, M.I.; de Haan, S.;
Ion Implantation Technology. Proceedings of the 11th International Conference
16-21 June 1996 Page(s):65 - 68
Digital Object Identifier 10.1109/IIT.1996.586125
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